

**RESPONSE UNDER 37 C.F.R. §1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1792**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant:** Kwang Su Choe, et al.      **Examiner:** Marianne L. Padgett  
**Serial No.:** 10/674,647      **Art Unit:** 1792  
**Filed:** September 30, 2003      **Docket:** YOR920030293US1 (16818)  
**For:** THIN BURIED OXIDES BY LOW-DOSE      **Dated:** November 16, 2009  
OXYGEN IMPLANTATION INTO MODIFIED  
SILICON

**Confirmation No:** 4796

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

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Sir:

In response to the Final Office Action dated September 15, 2009, Applicants respectfully request that the following amendments and remarks be considered for entry as a matter of record in the above referenced application.

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**CERTIFICATE OF ELECTRONIC FILING**

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on November 16, 2009.

Dated: November 16, 2009



Harry Andrew Hild Jr.